

**FINE**

**CLAD**

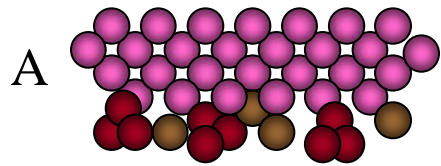
*CLAD MATERIAL ~*

**FINE CLAD is a solution for high density,  
low cost PWB.**

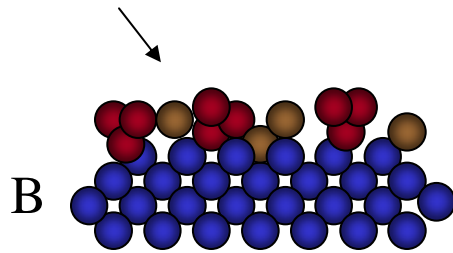
# **Principle of bonding technique**

# Principle of bonding technique

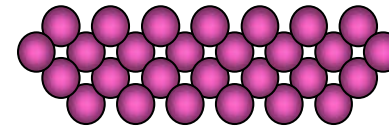
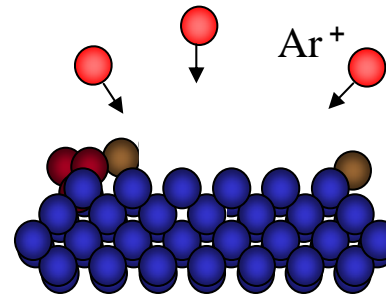
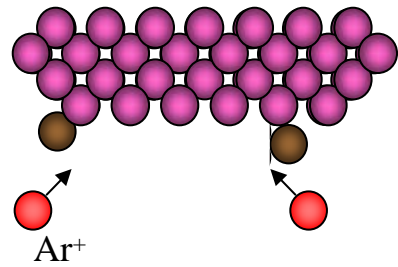
Step 1  
Material A, B  
In vacuum



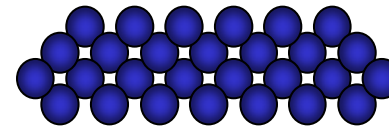
Oxide and adsorbate



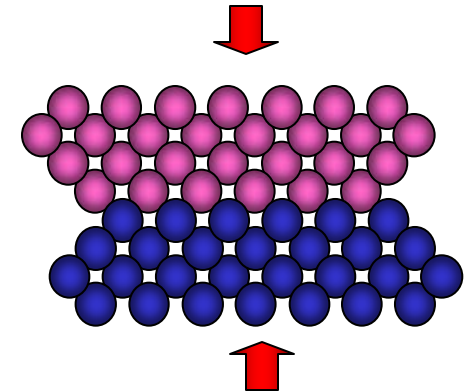
Step 2  
Surface activated  
treatment



Activated  
surface

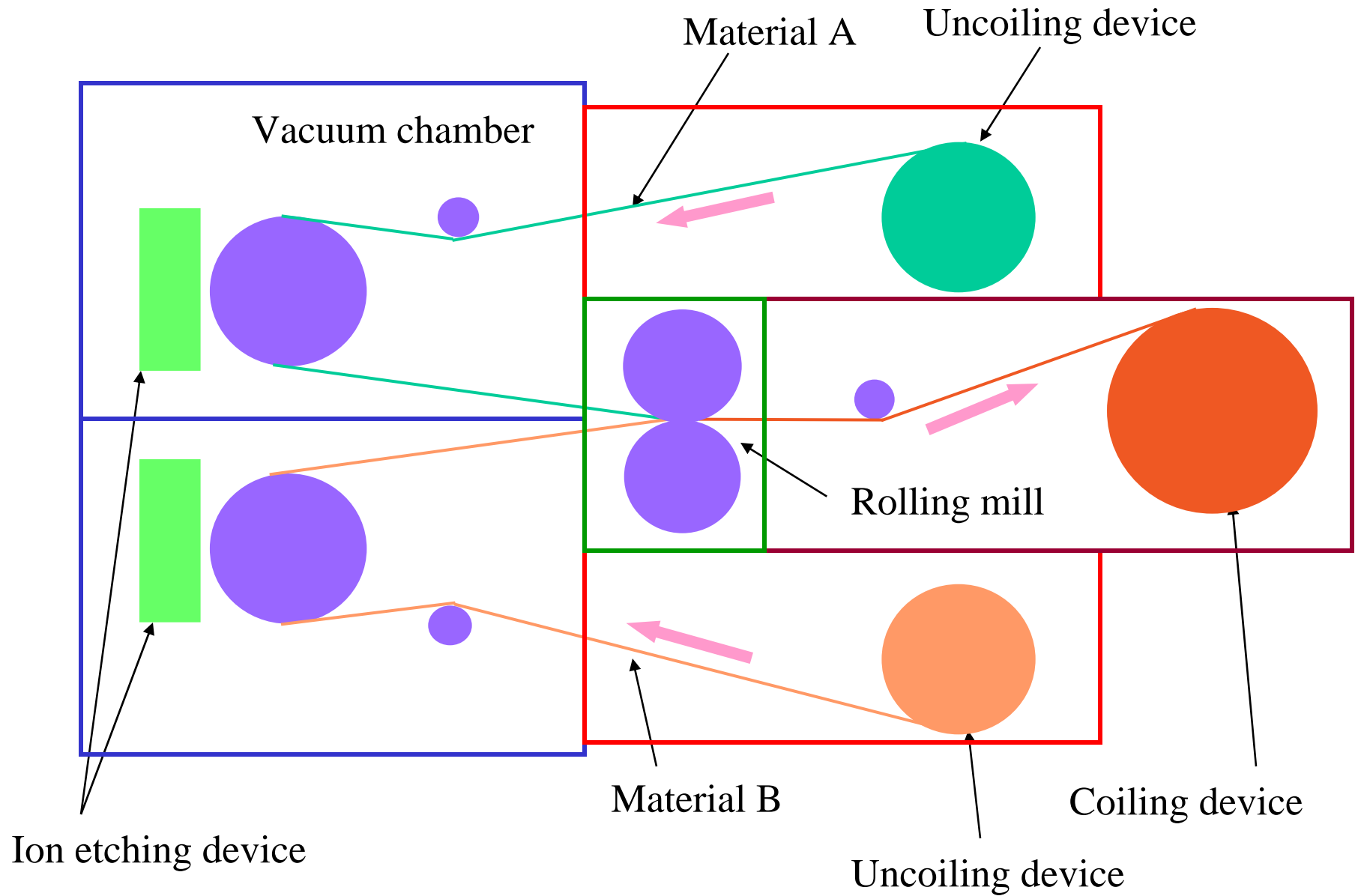


Step 3  
Roll bonding



# **Manufacturing process**

# Manufacturing process



# **Features of FINE CLAD**

**Feature 1**

**Flat and clean bonding interface**

**Feature 2**

**A variety of possible metal combinations**

**Feature 3**

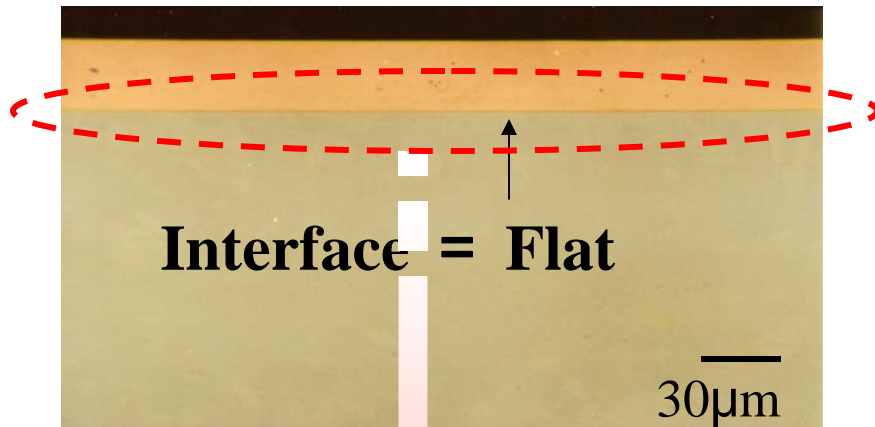
**Pattern roll bonding**

# **Feature 1 Bonding interface**

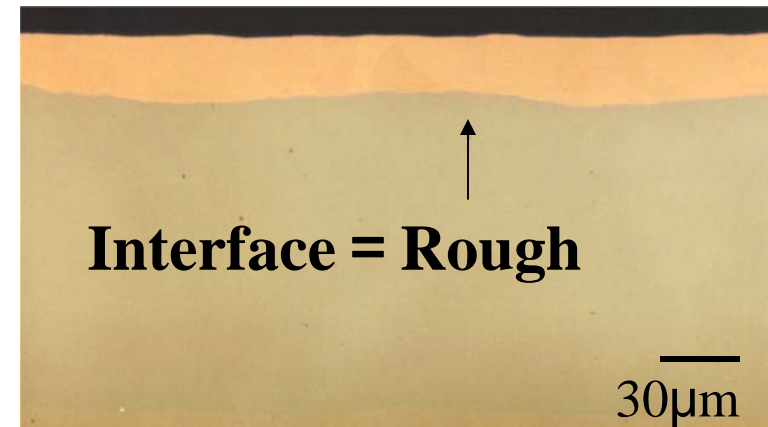


# Cross section of FINE CLAD

**Cu/Ni FINE CLAD**



**Conventional Cu/Ni clad**



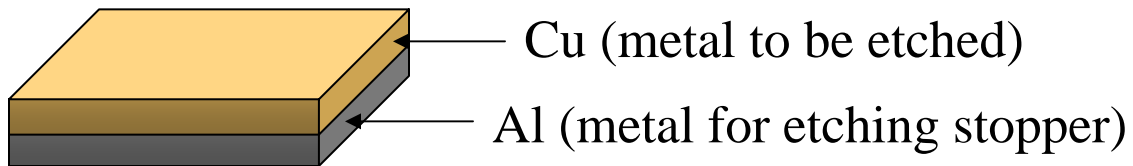
**Is there alloy layer in the interface?**

**No!** → **Suitable for selective etching**

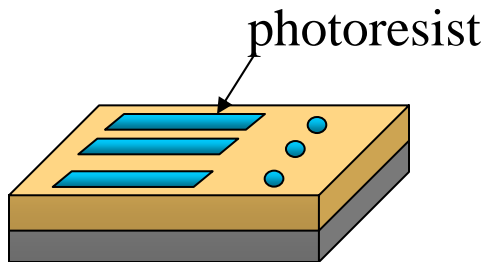
# Outline of selective etching

( Selective etching : Etching only one side metal of clad material )

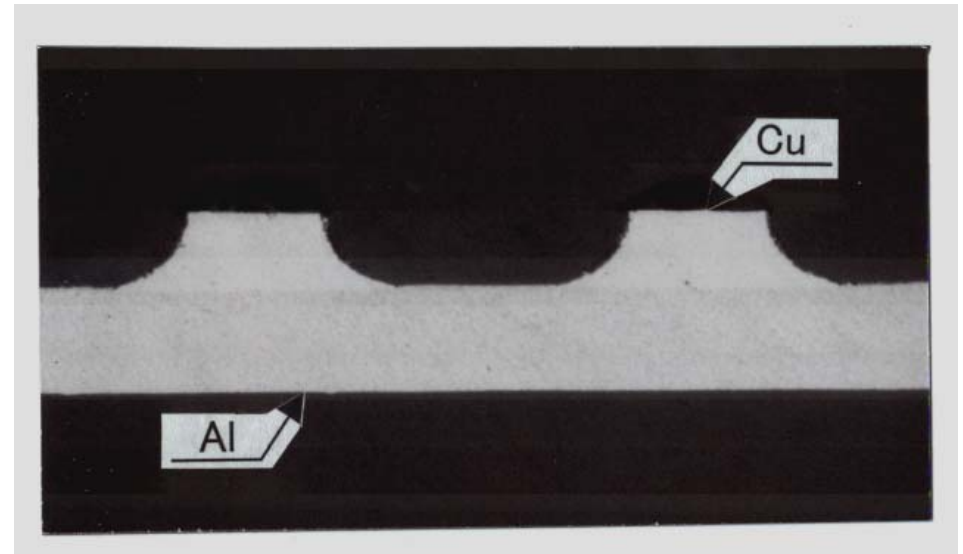
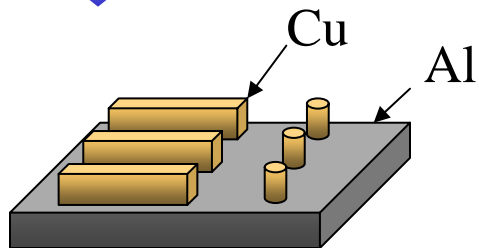
Example : Cu/Al FINE CLAD



↓ Patterning photoresist



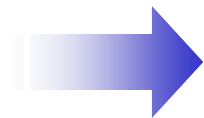
↓ Selective etching Cu



Cross section of Cu/Al after Cu selective etching

## Metal combinations for selective etching

Etching metals	Metals for etching stopper	Etchant for selective etching
Cu	Al	Acid etchant (sulfuric acid etc.)
Al	Cu	Sodium hydroxide etchant etc.
Cu	Ni	Sulfuric acid + hydrogen peroxide etchant Ammonium persulfate etchant Commercial Alkaline etchant
Ni	Cu	Commercial Ni etchant
Cu, SUS	Pd, Ag	Ferric chloride etchant
Ag, Cu	SUS	Ferric nitrate etchant

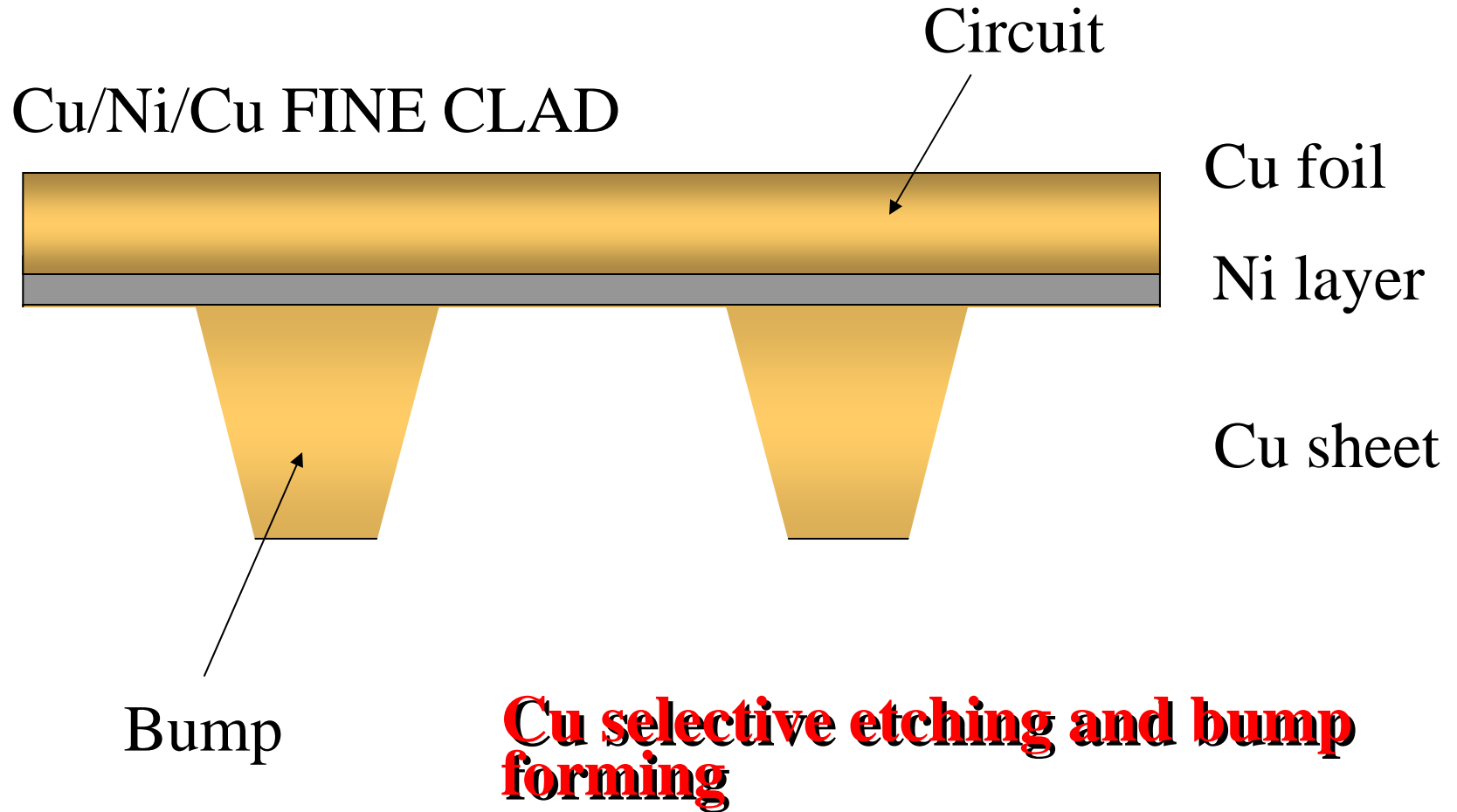


What is the best use of FINE CLAD by using these merit?

# **FINE CLAD for Printed Wiring Board**

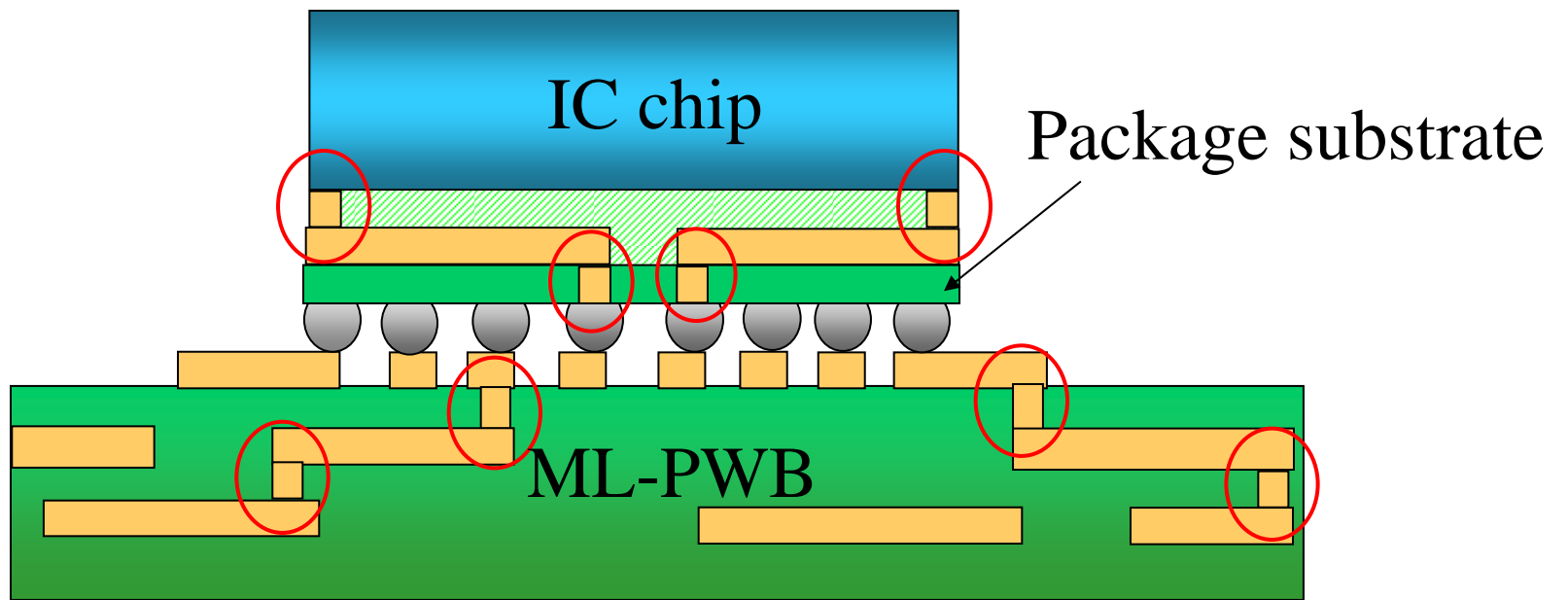
**Etching bump provides high density,  
low cost PWB**

# Structure and etching process



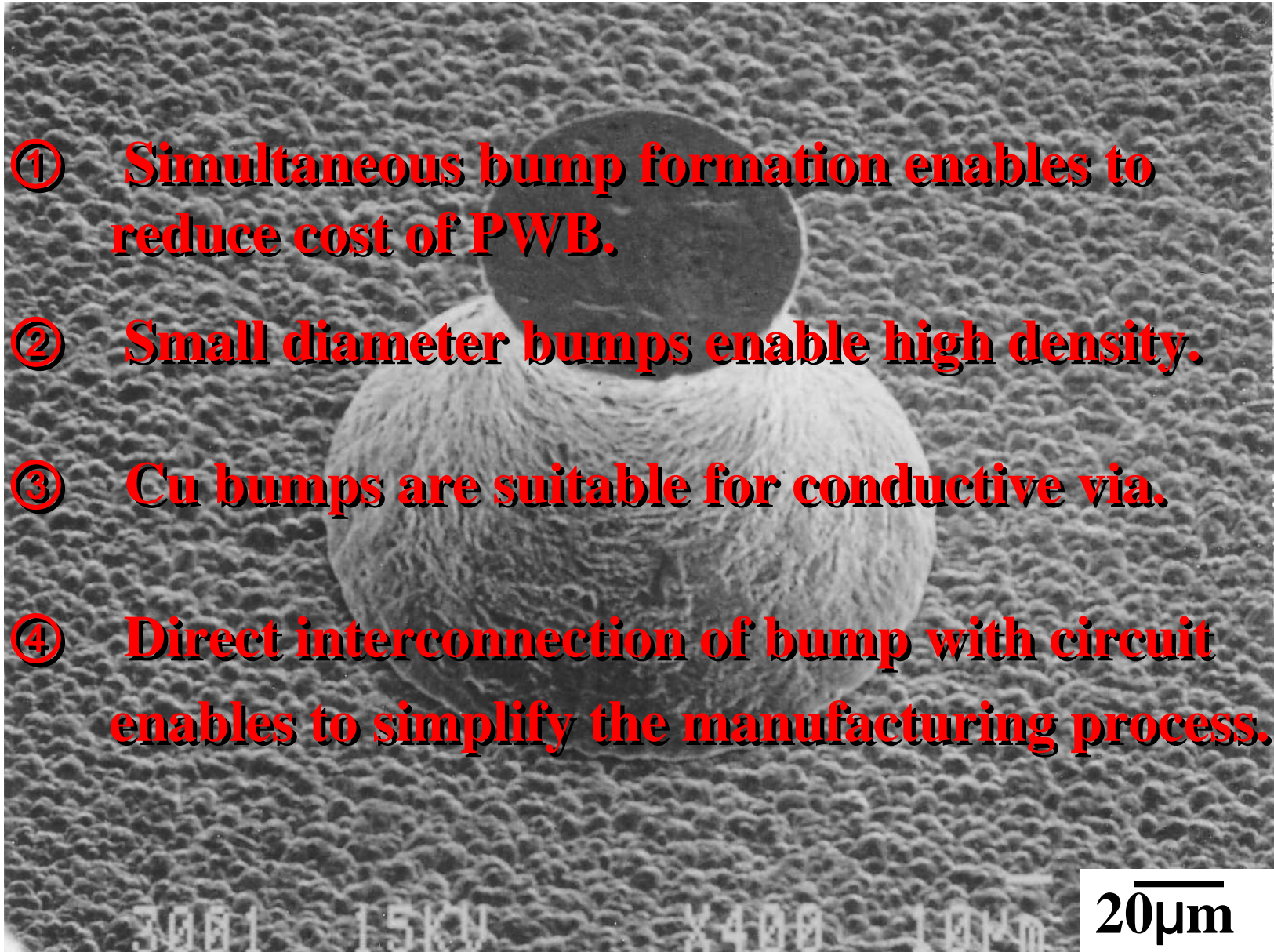
Cu for circuit : 10 ~ 35 $\mu$ m thickness  
Ni layer : 0.5 ~ 3  $\mu$ m (electrolytic plating)  
Cu for bump : 50 ~ 150  $\mu$ m

## Role of etched Cu bump

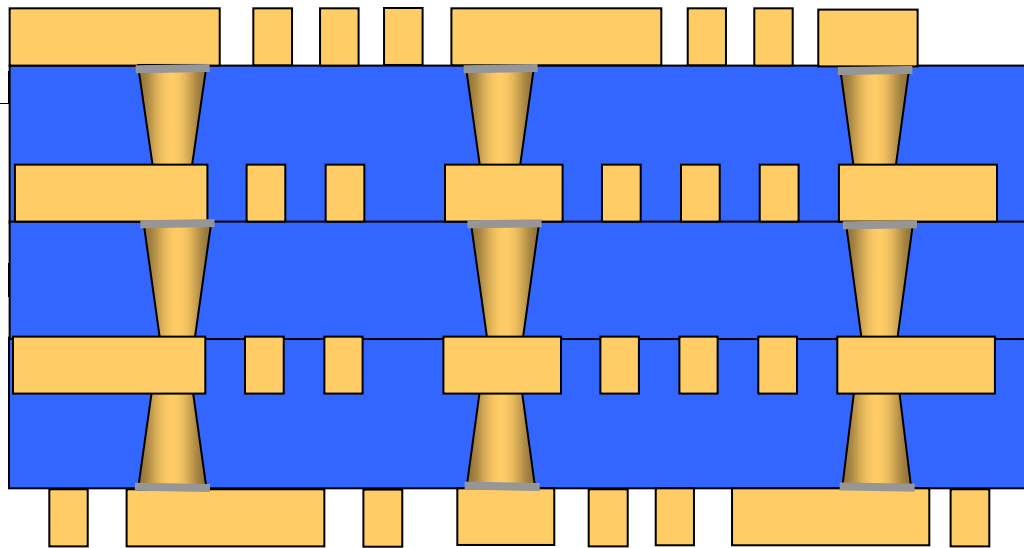


## Features of etched Cu bump

- ① **Simultaneous bump formation enables to reduce cost of PWB.**
- ② **Small diameter bumps enable high density.**
- ③ **Cu bumps are suitable for conductive via.**
- ④ **Direct interconnection of bump with circuit enables to simplify the manufacturing process.**



# Process of multi layer PWB



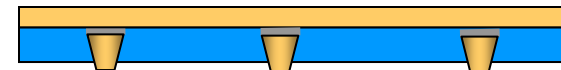
Cu/Ni/Cu clad



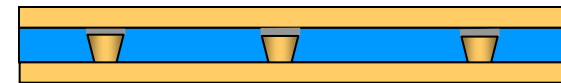
Bump forming and Ni removing



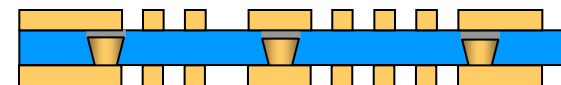
Laminating resin



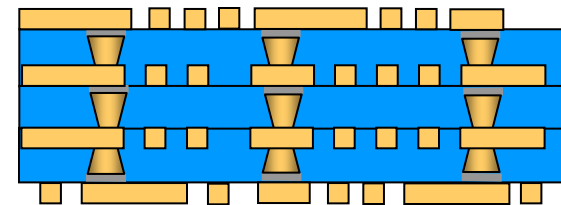
Hot press



Patter forming



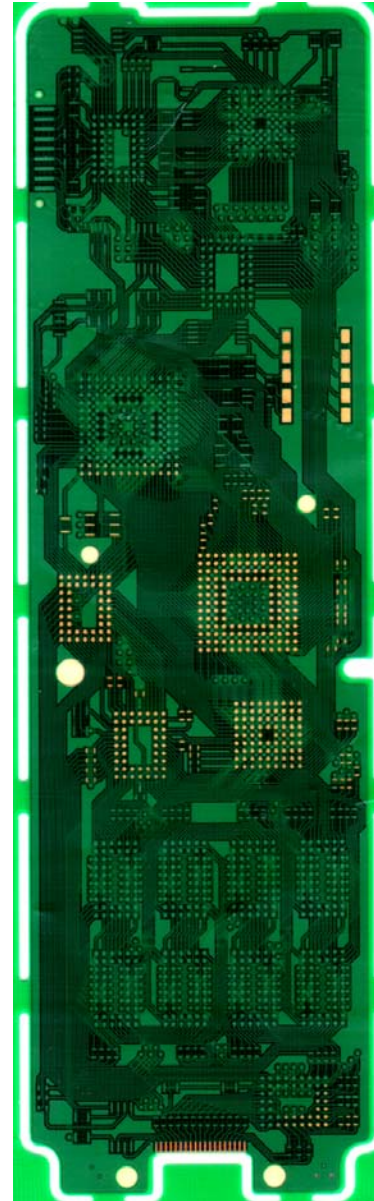
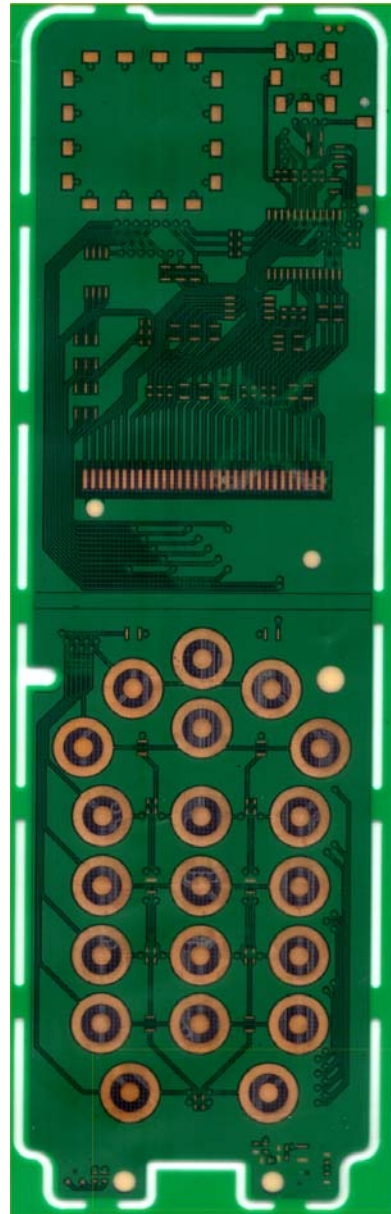
Repeat





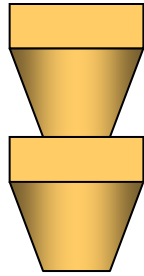
# ML-PWB

( for mobile  
phone )

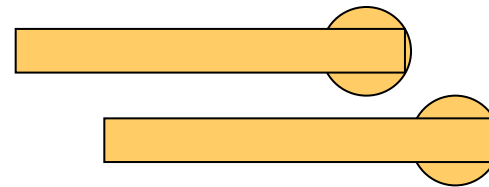


Produced by NORTH corp., Japan  
(layer : 1+2+1)

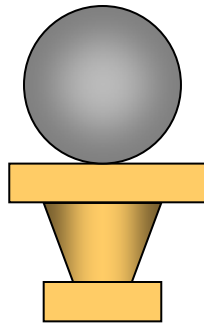
# Flexibility of products design



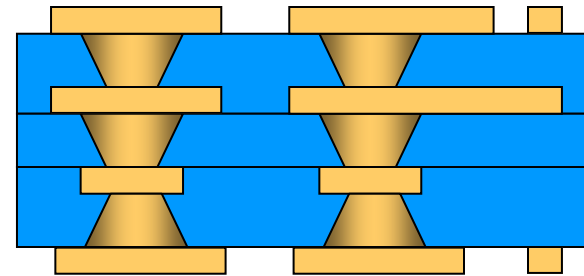
- **Stacked via**



- **Landless design**



- **Pad on via**



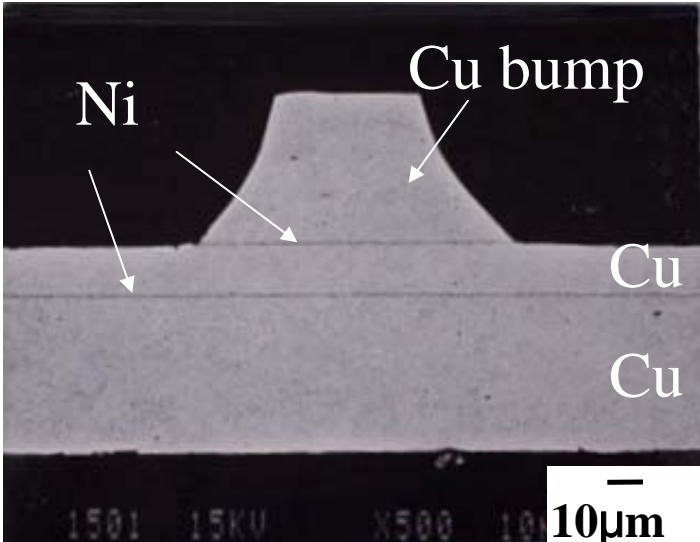
- **All IVH**

**Application to the package substrate**

# Etched Cu bump



**Etched Cu bump**



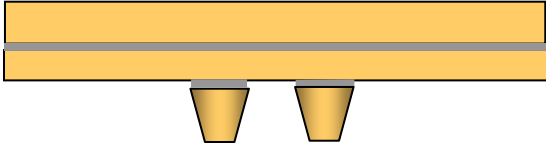
**Cross section**

# Package substrate

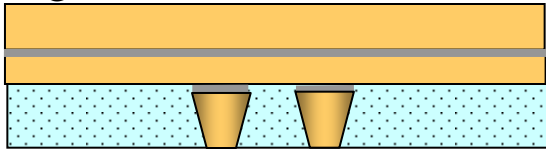
Cu/Ni/Cu/Ni/Cu clad



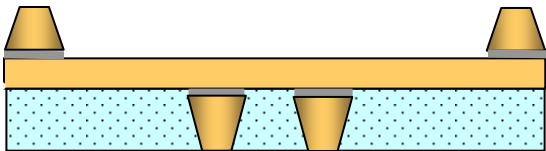
Bump forming ↓



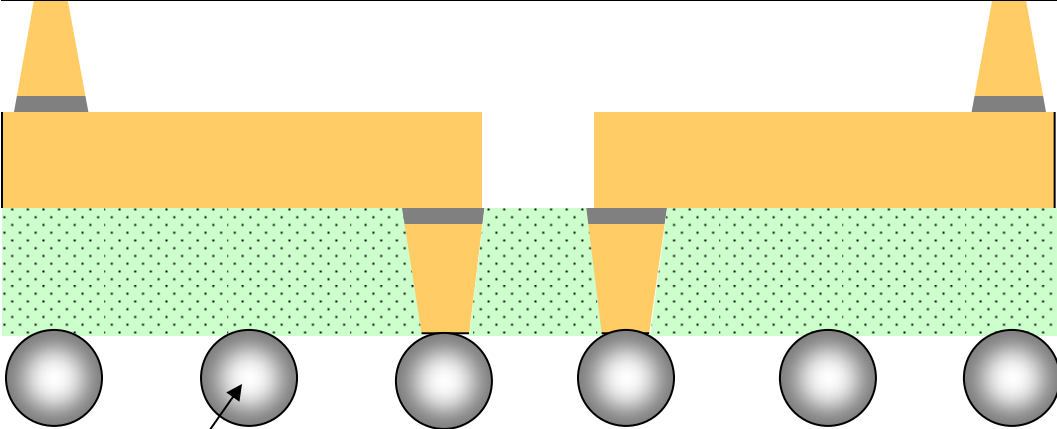
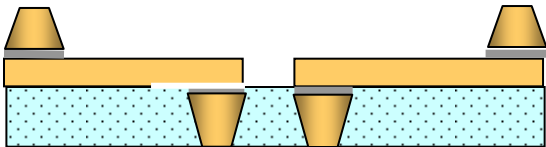
Laminating Insulating resin ↓



Bump forming ↓

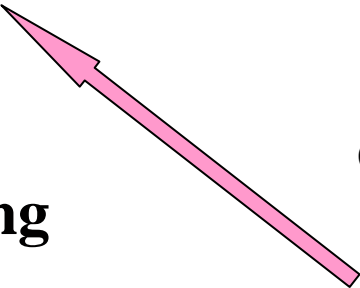


Circuit forming ↓

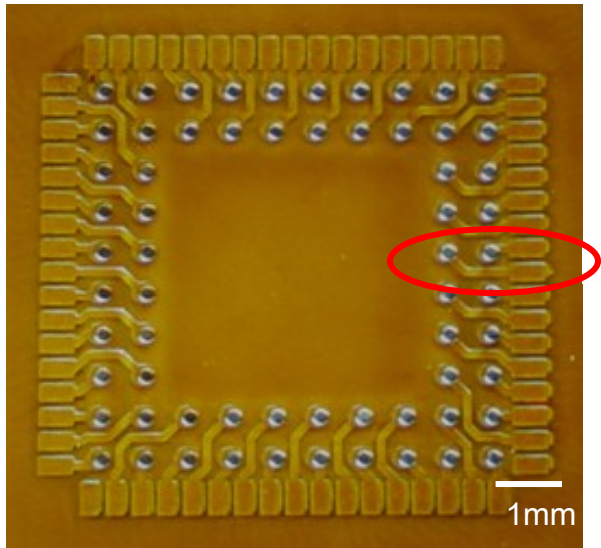
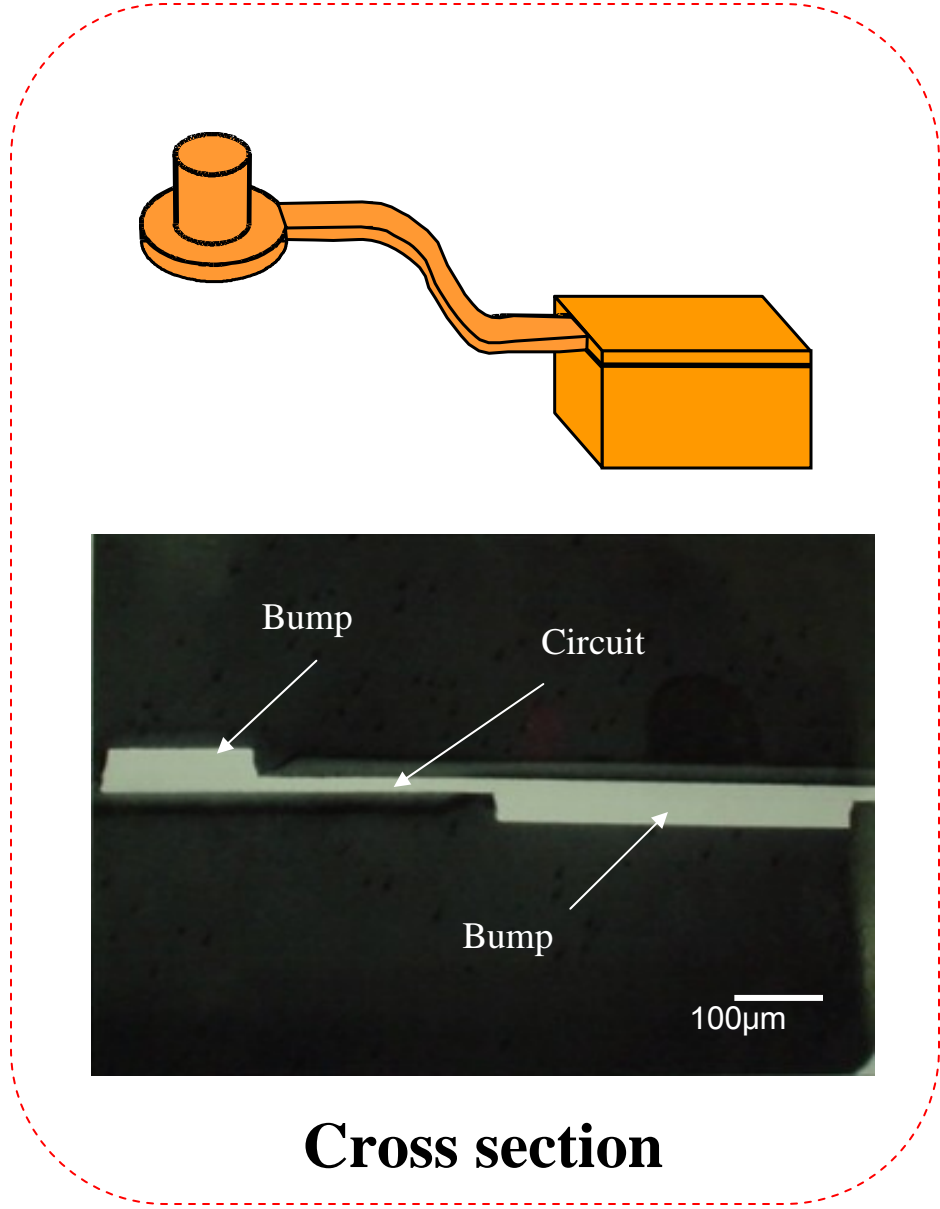
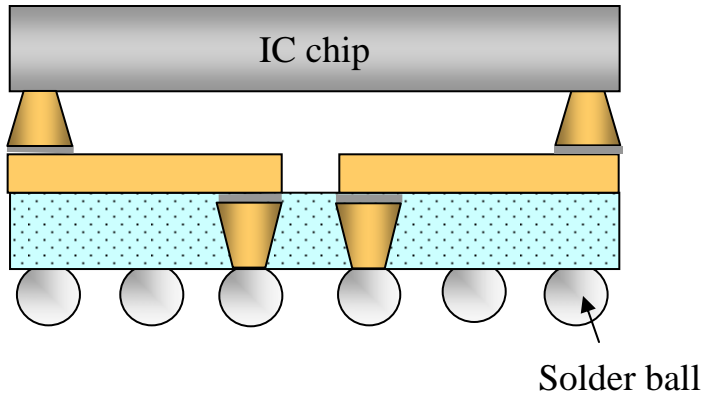


Solder ball

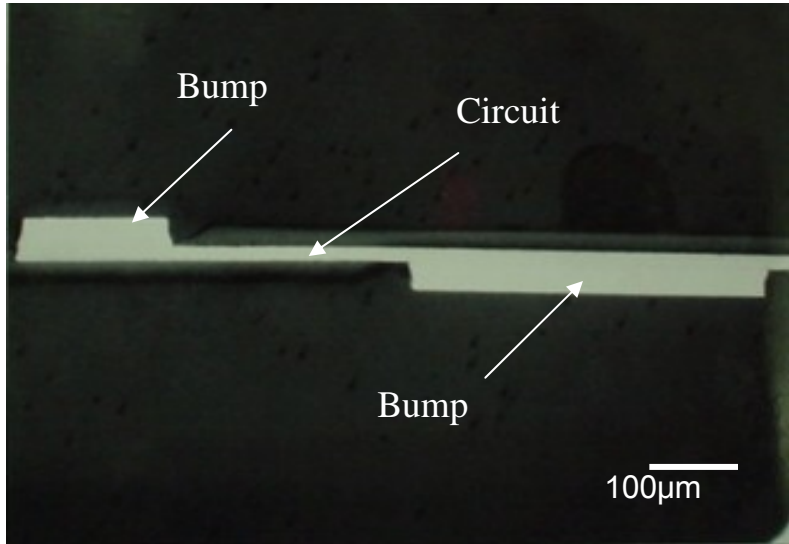
Package



# Package substrate



**Substrate sample  
(resin : polyimide)**

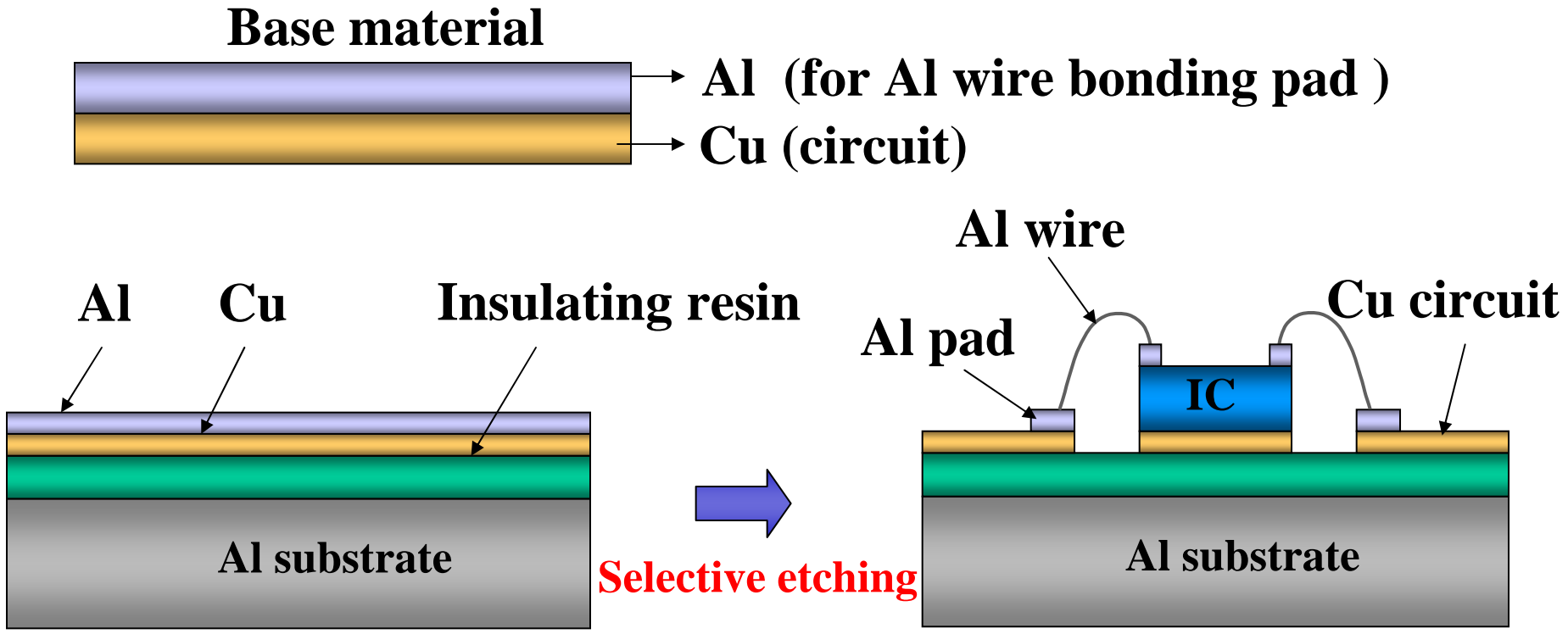


**Cross section**

# Material for power module substrate

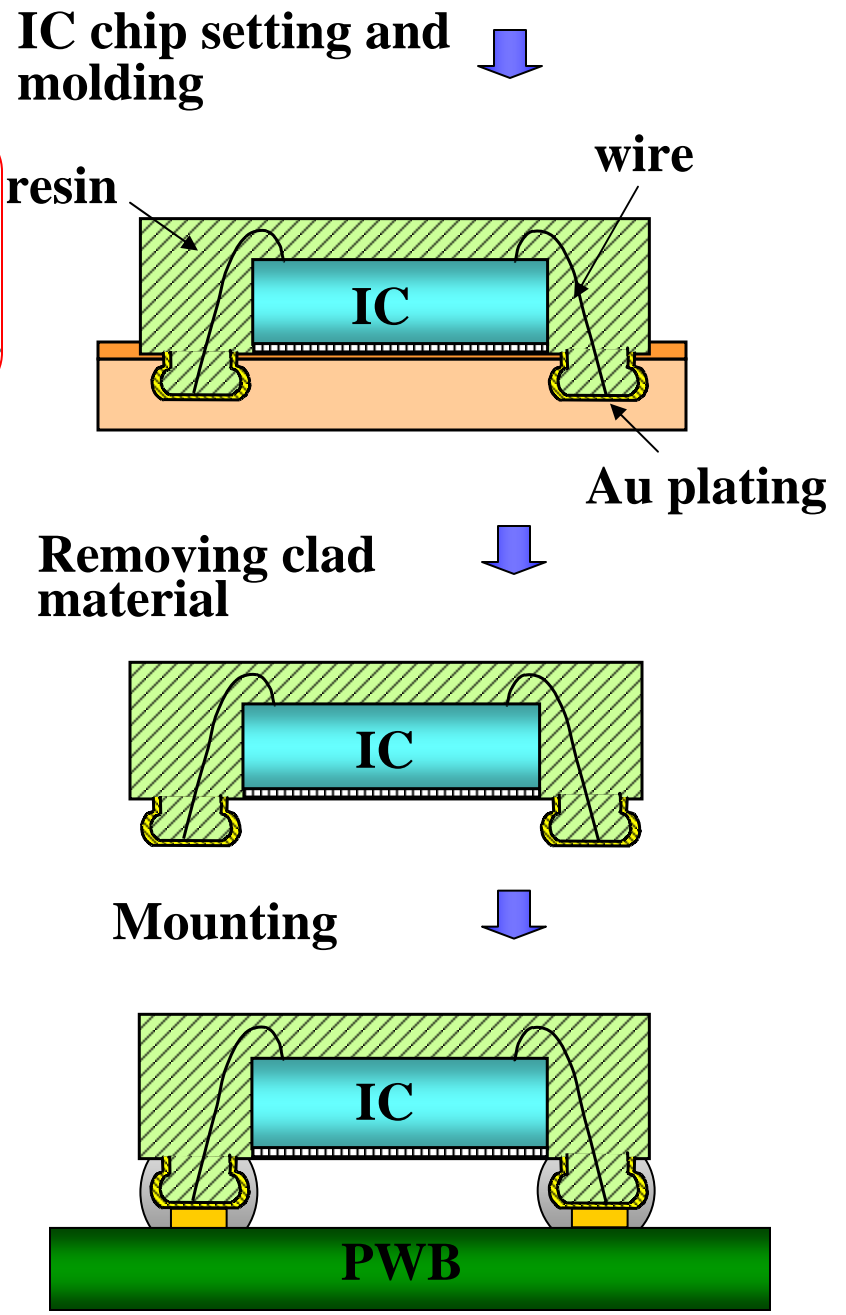
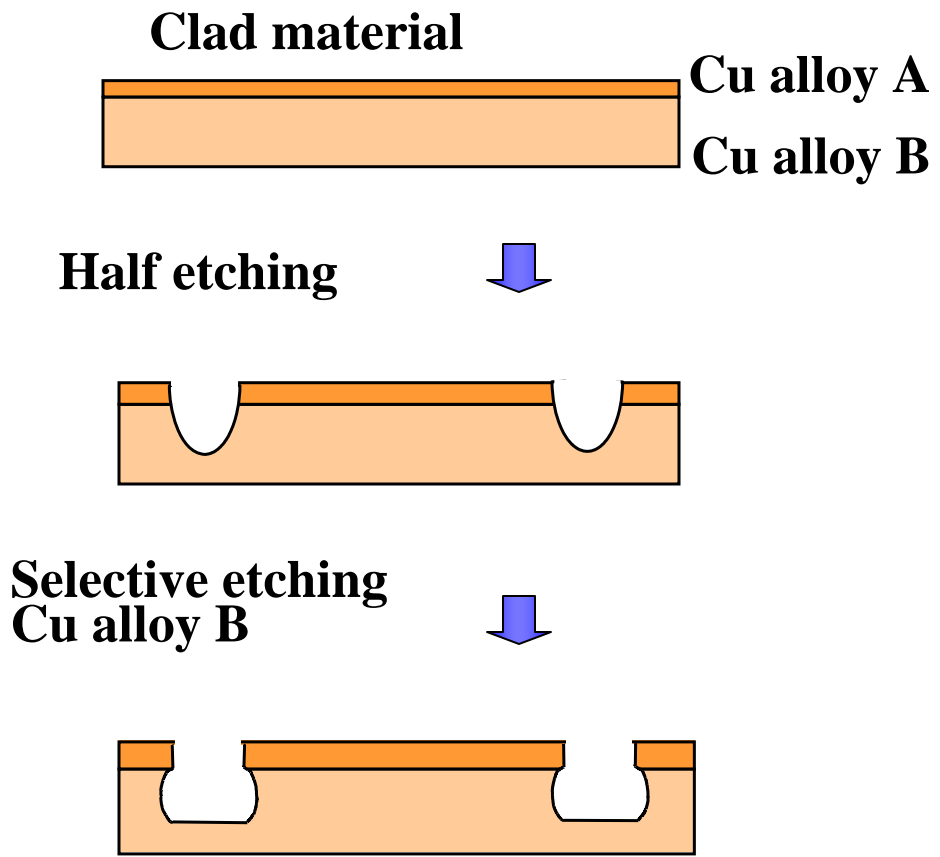
Structure : Cu/Al

Merit : Possible to form Al pad for Al wiring and Cu circuit.



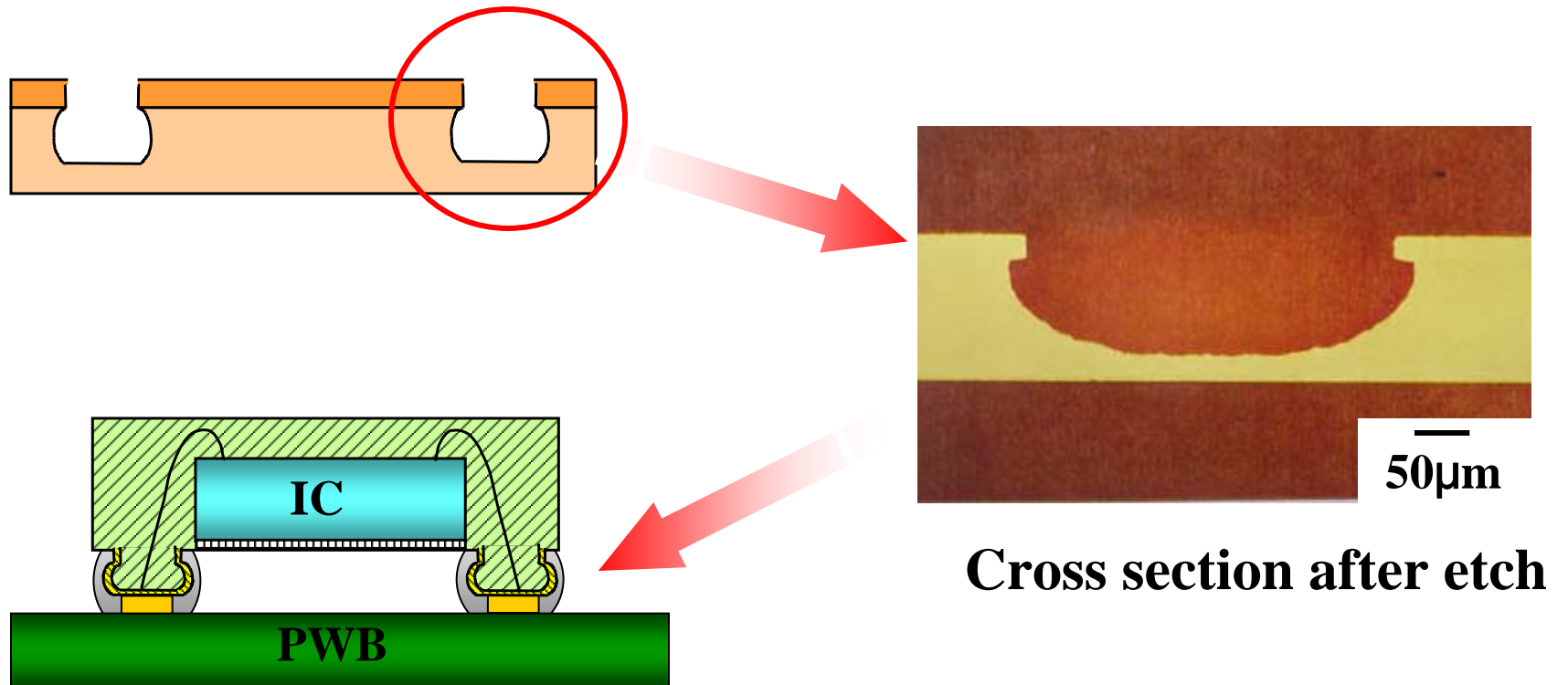
# Bump formation for QFN

**Structure : Cu alloy / Cu alloy**  
**Merit : Possible to improve the reliability of QFN mounting.**





## Bump formation for QFN

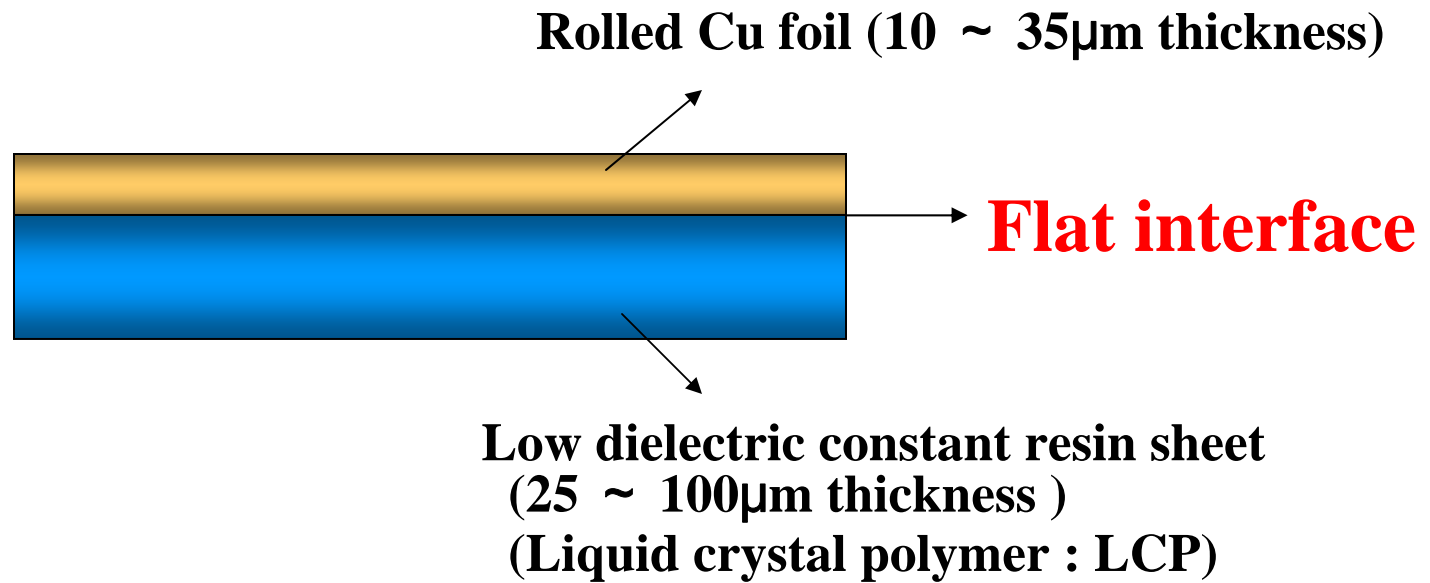


**Reverse mushroom shape bumps improve the mounting reliability.**

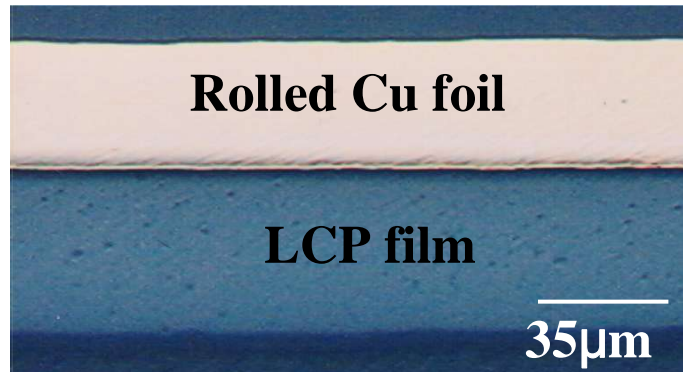
# Copper Laminated Resin sheet

**FINE CLAD changes the RF PWB design.**

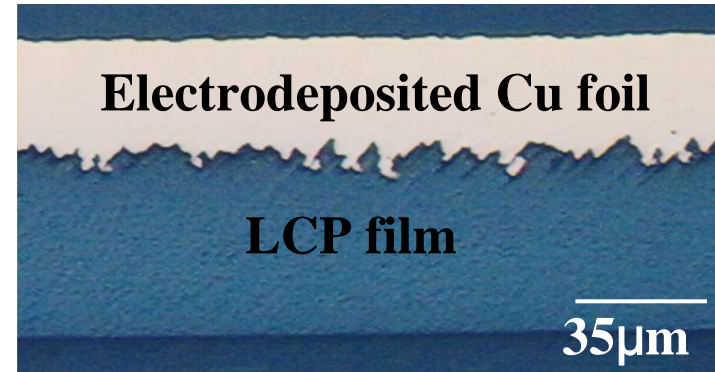
# Structure



# Advantages



Developed material



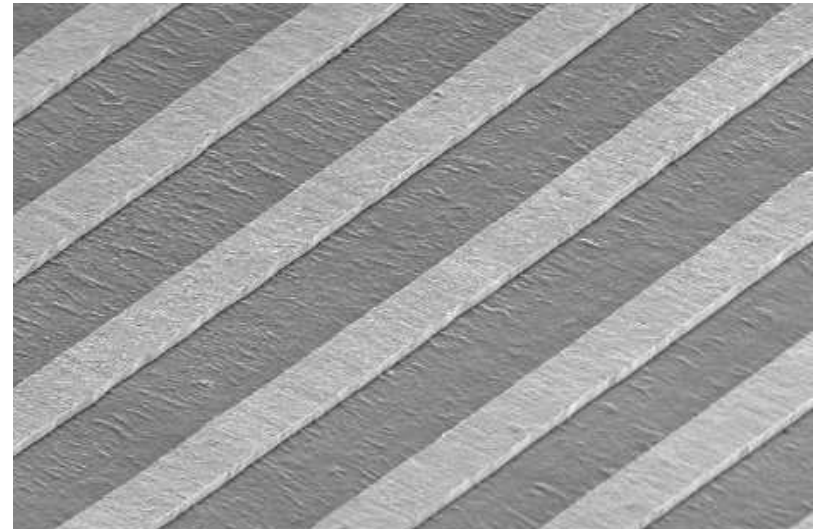
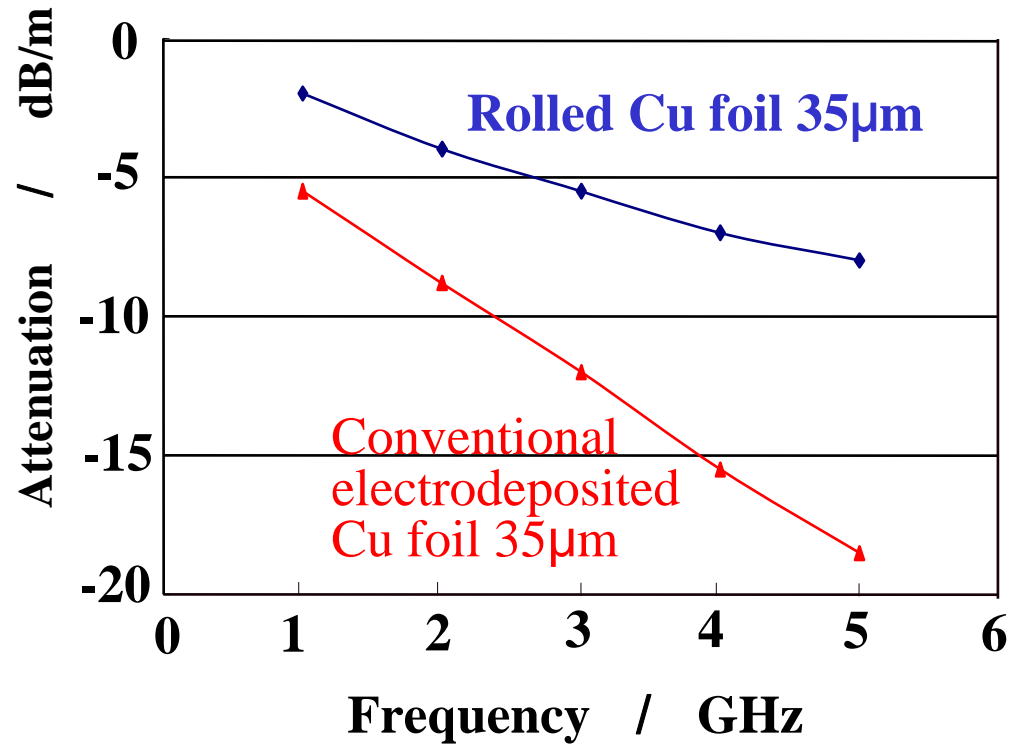
Conventional hot press type

Cross section of Cu laminated resin sheet

## Advantages of developed material

	Developed material	Conventional
Interface	<b>Flat</b>	<b>Rough</b>
Skin resistance	<b>Low</b>	<b>High</b>
Accuracy of pattern	<b>Excellent</b>	<b>good</b>

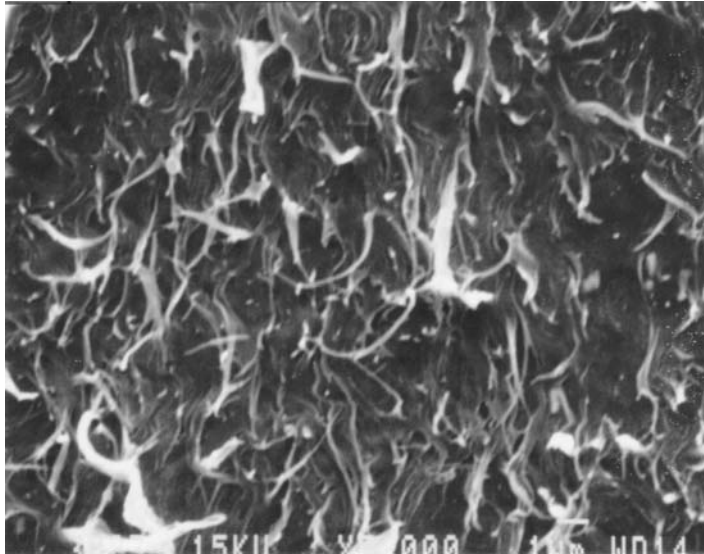
# High frequency characteristics



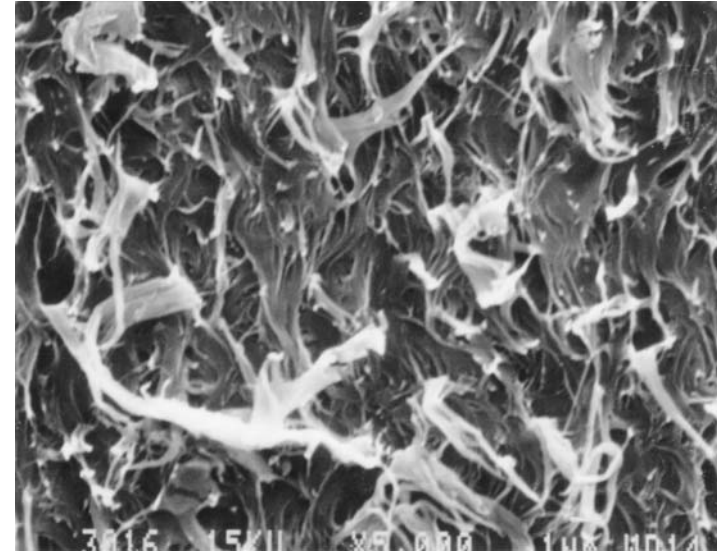
Cu foil : 7μm thickness  
LCP film: 50μm thickness  
L/S : 50μm / 50μm

## Peeled face after peeling test

Peeling strength : over 600g/cm at 180° peeling test



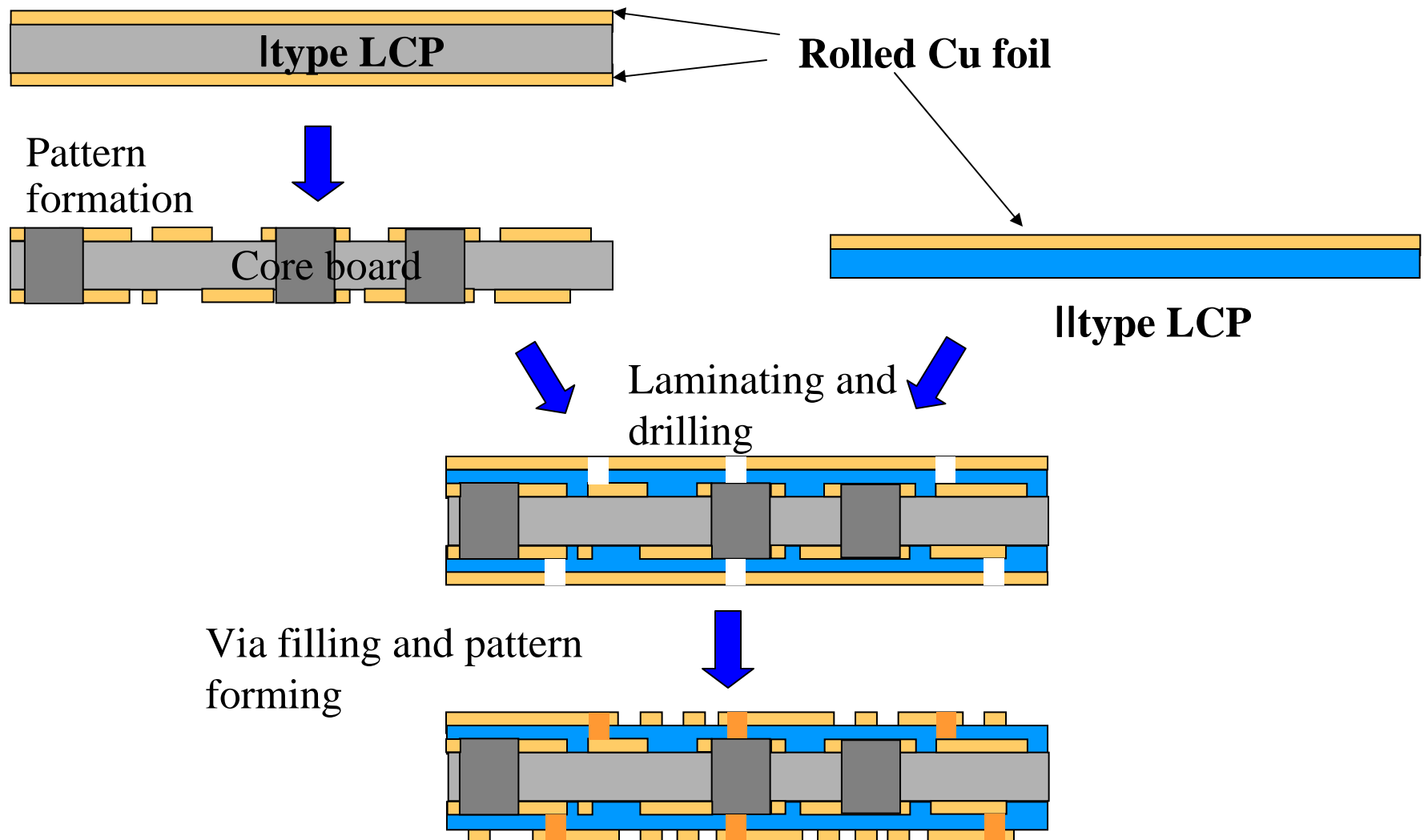
Cu side  
( LCP is remained on Cu )



LCP side  
(LCP is fractured at inside )

# Application to multi-layer PWB

## Manufacturing process of all LCP PWB



## Features

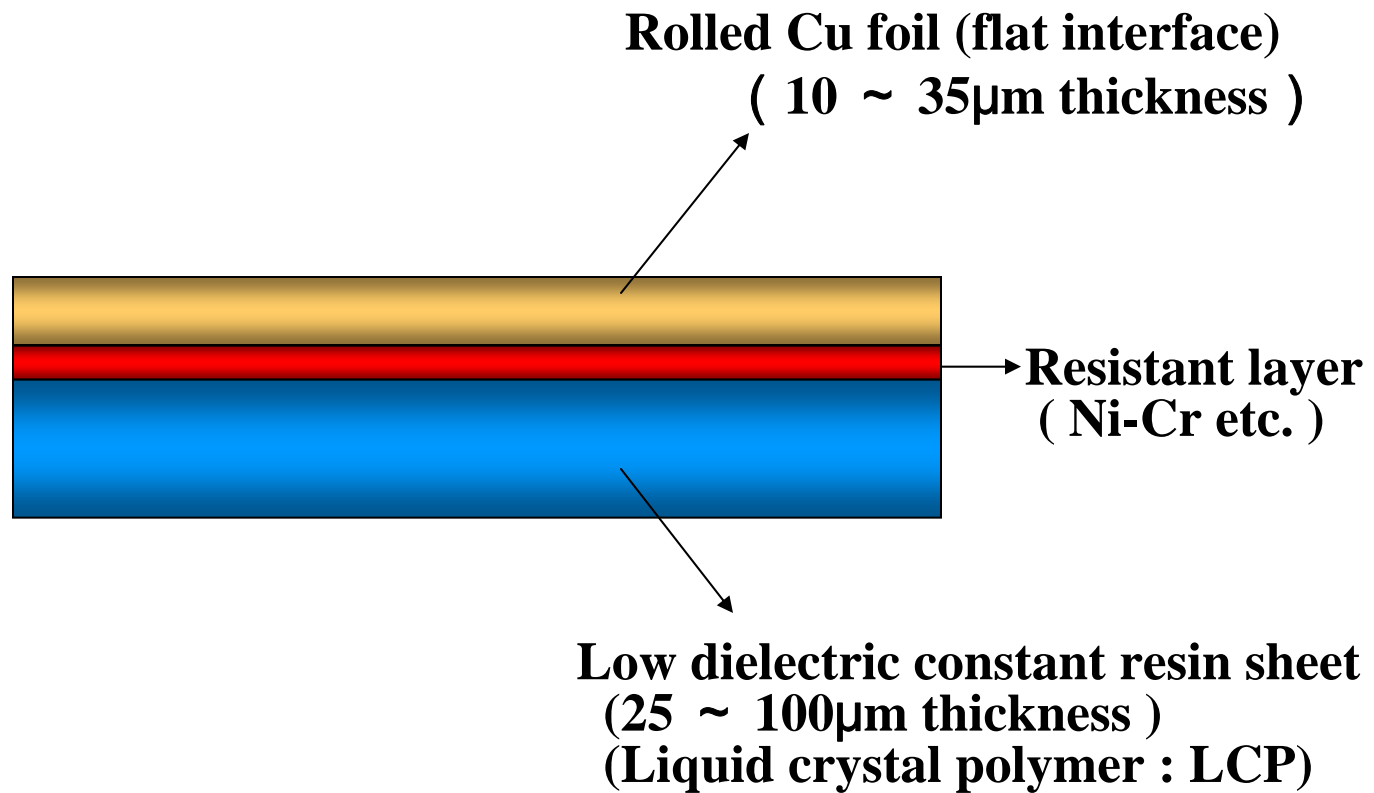
- ① **Flat interface reduces skin resistance.**
- ② **Flat interface enables to form fine pitch pattern.**
- ③ **Combination with low dielectric constant resin sheet enables the application to RF PWB.**
- ④ **A variety of resin sheets are available.**



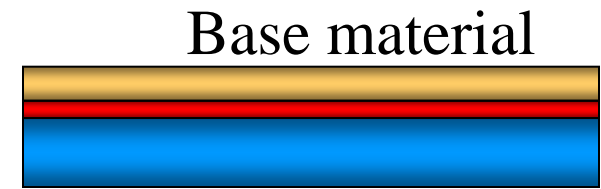
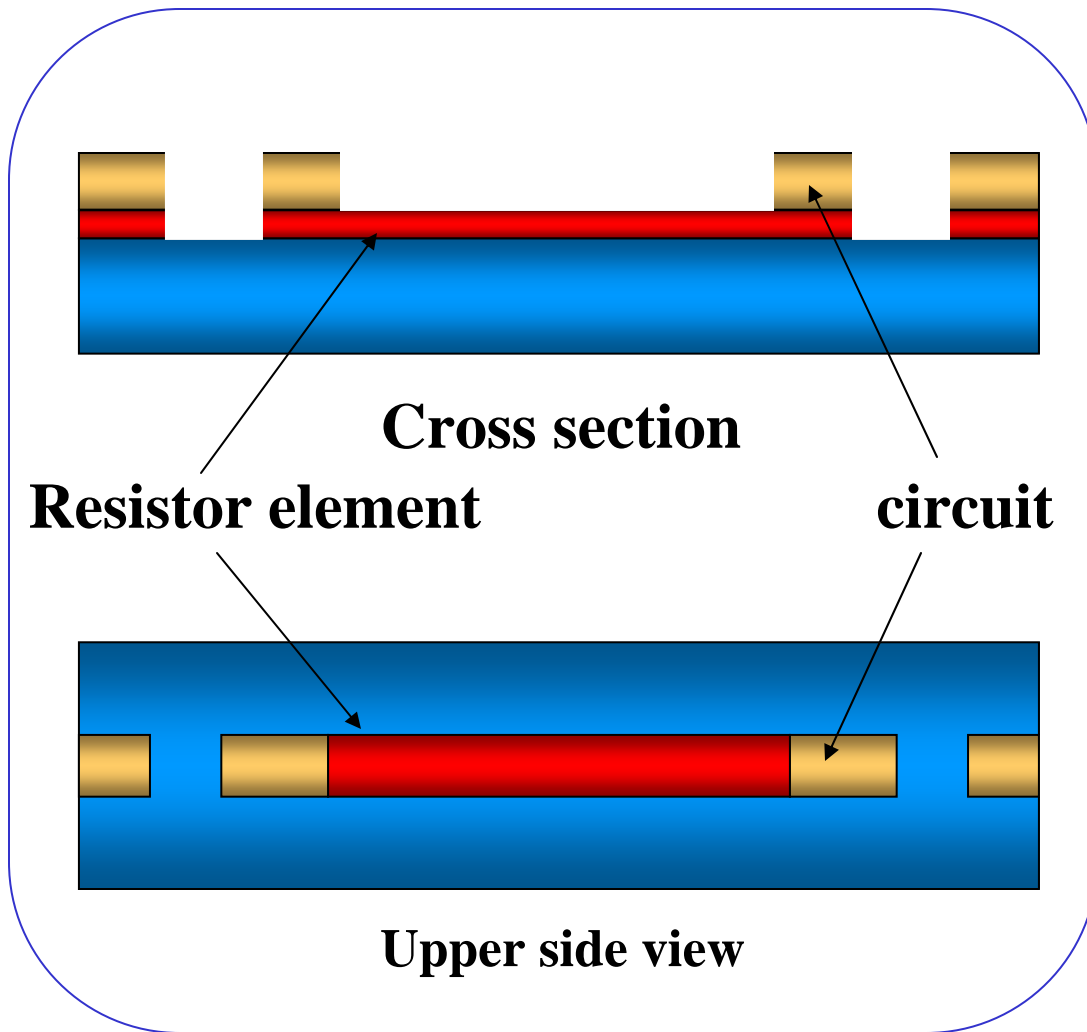
## **Multi-layer sheet for embedded resistor**

**FINE CLAD provides  
the embedded passive devices.**

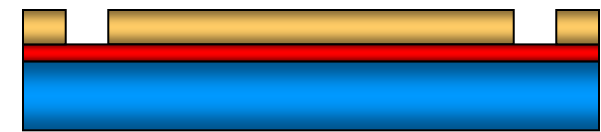
# Structure



# Process for resistor element



Cu selective etching ↓



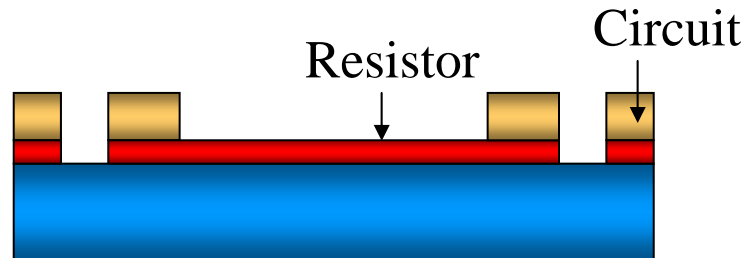
Resistant layer etching ↓



Cu selective etching

A large blue arrow points from the right side of the diagram towards the 'Upper side view' of the resistor element, indicating the final step in the process.

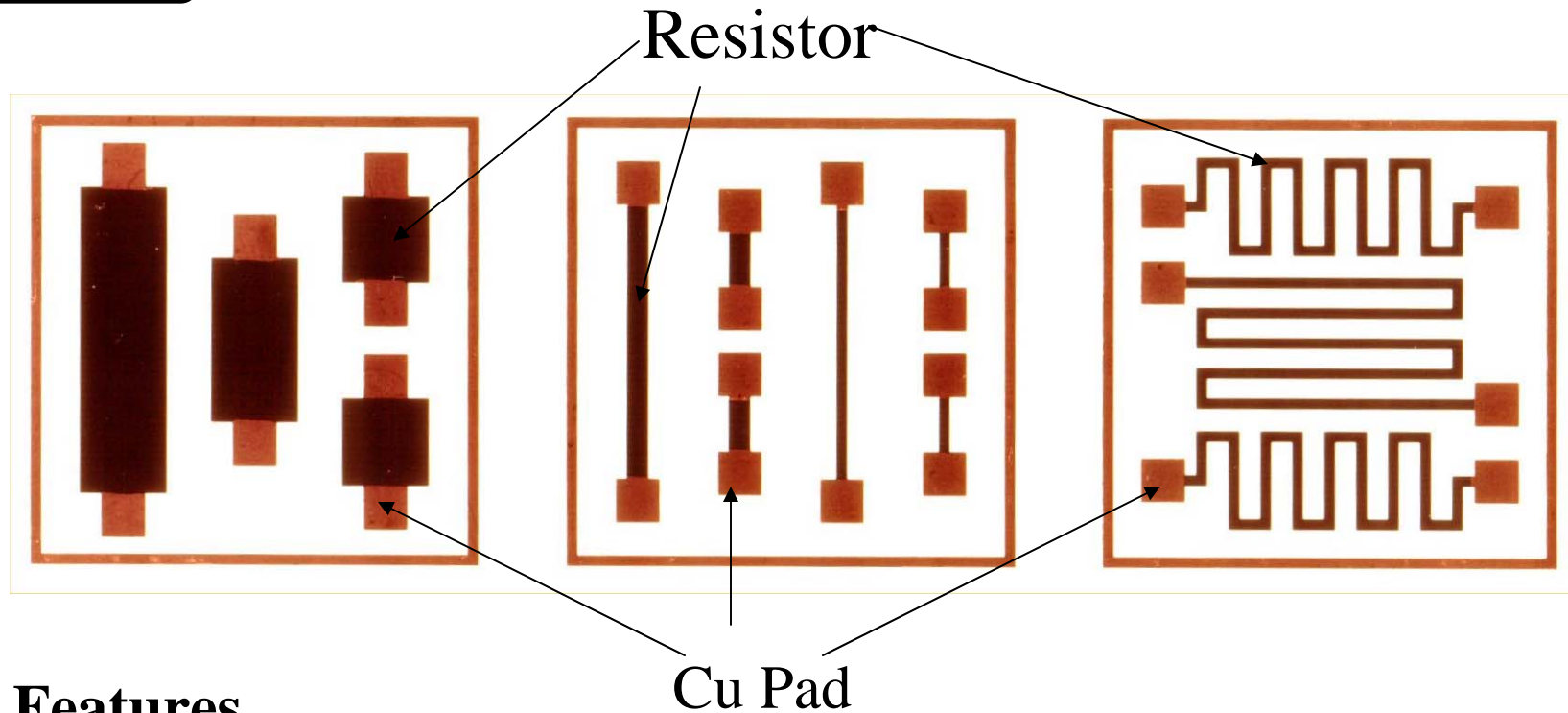
# Specifications



## Specifications

Resistive material	Ni-Cr
Thickness of layer	10 ~ 200nm
Sheet resistance	25, 50, 100 $\Omega$ / $\square$

# Features



## Features

- ① Low TCR material is used.
- ② Resistor can be formed only by etching process.
- ③ Flat thin film enables to improve the accuracy of etching.

# **Feature 2 Materials combinations**

## Manufacturing range

Material thickness	10 $\mu$ m ~ 1mm
Product thickness	30 $\mu$ m ~ 1mm
Product width	2.5 ~ 600mm $\times$ Coil

# Materials combinations

	Al	Cu	Ni	Ag	Au	Pd	Pb	Sn
Al	●	●	●	—	—	—	●	●
Cu	●	●	●	●	●	—	—	●
Ni	●	●	●	—	—	—	—	●
Ag	—	●	—	—	—	●	—	—
Au	—	●	—	—	—	—	—	—
Pd	—	—	—	●	—	—	—	—
Pb	●	—	—	—	—	—	—	—
Sn	●	●	●	—	—	—	—	—
Steel	●	●	●	●	—	●	●	●
Ti	●	●	—	●	●	—	●	—
Mo	●	●	—	—	—	—	—	—

Al :Including 1000, 2000, 3000,4000,5000 alloy

Cu :Including 1020, 1100, 1201, 5210 alloy

Steel :Including SUS304, SUS316,SUS430, Invar, 42alloy etc.

— :Bonding has not been verified.



# Mechanical properties of clad before and after cladding

	Material	Thickness (mm)	Hardness (Hv)	Tensile strength(N/mm <sup>2</sup> )
Before cladding	SUS304	0.201	170	703
	Al	0.056	24	59
After cladding	SUS304	0.200	173	572 <sup>*</sup>
	Al	0.055	25	
Before cladding	steel	0.271	137	343
	Al	0.030	25	59
After cladding	steel	0.270	139	316 <sup>*</sup>
	Al	0.029	26	
Conventional clad	SUS304	0.243	287	744 <sup>*</sup>
	Al	0.051	24	

\* Strength of clad material

**Mechanical properties of raw material have hardly changes before and after cladding.**

# Drawing and ironing of FINE CLAD

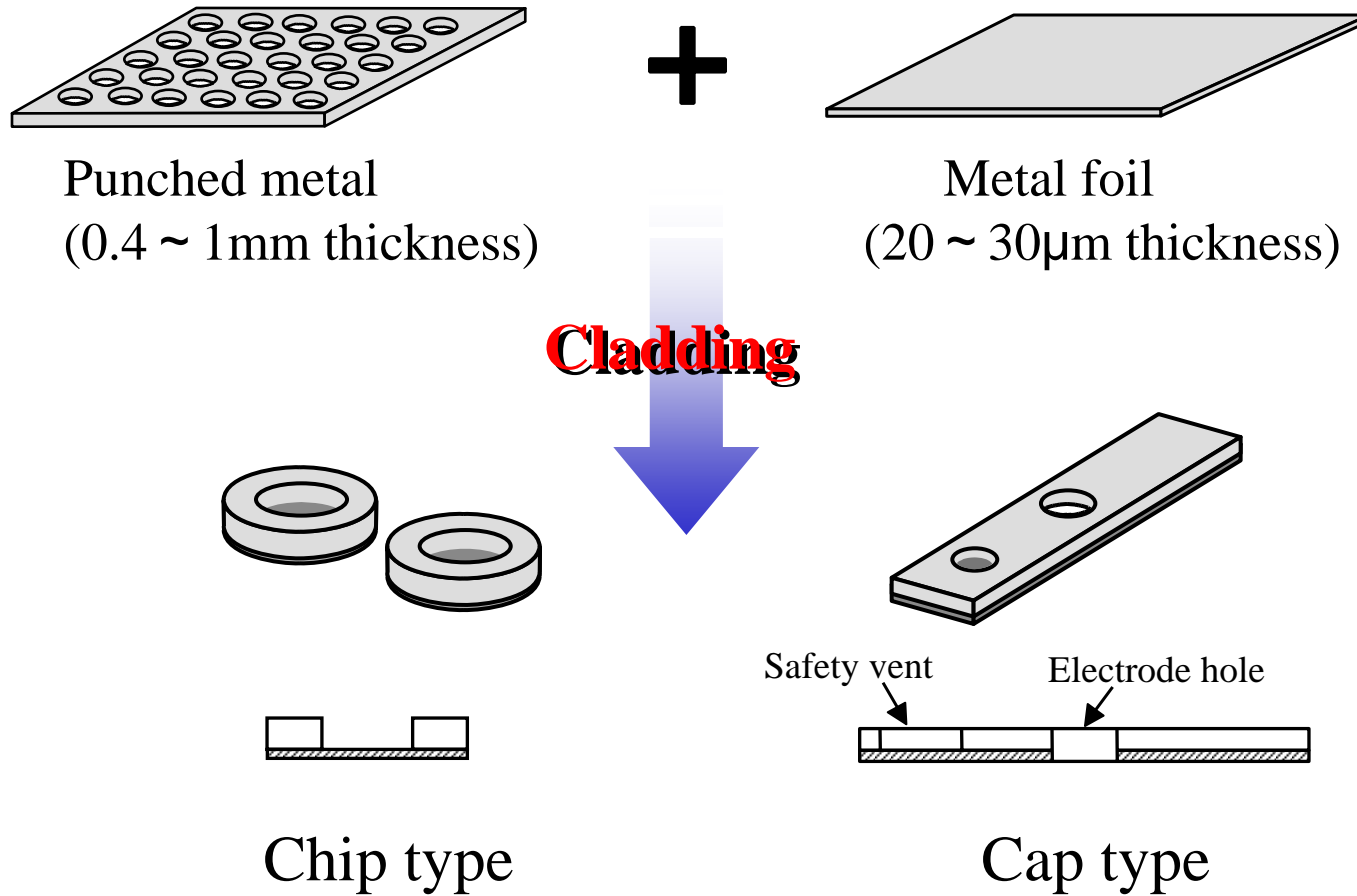


## **Feature 3 Pattern roll bonding**

**Pattern roll bonding 1**

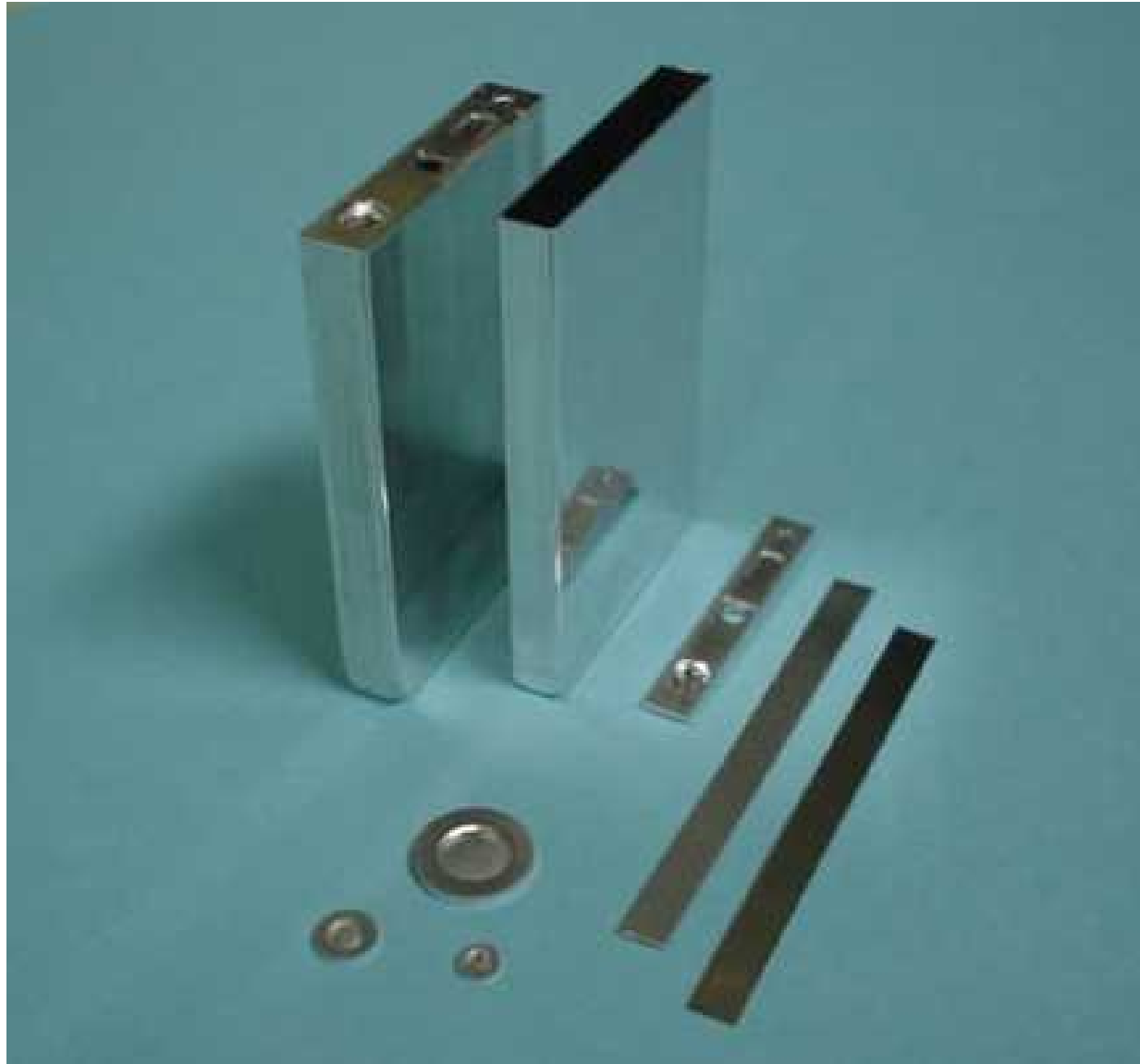
**~ safety vent ~**

# Process of safety vent



Manufacturing process of safety vent for  
Li ion secondary battery

## Parts for Li ion secondary batteries

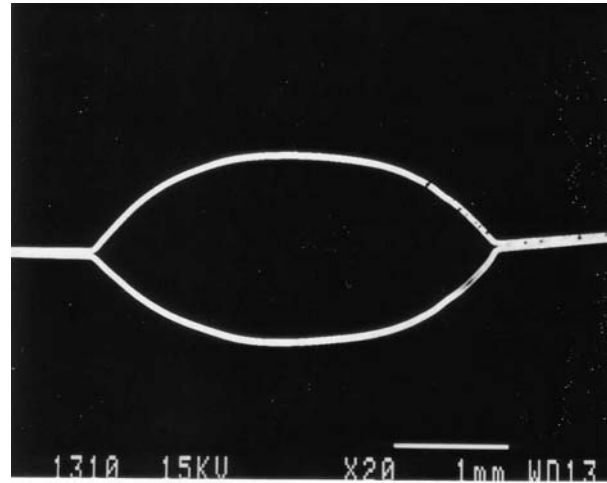


**Pattern roll bonding 2**

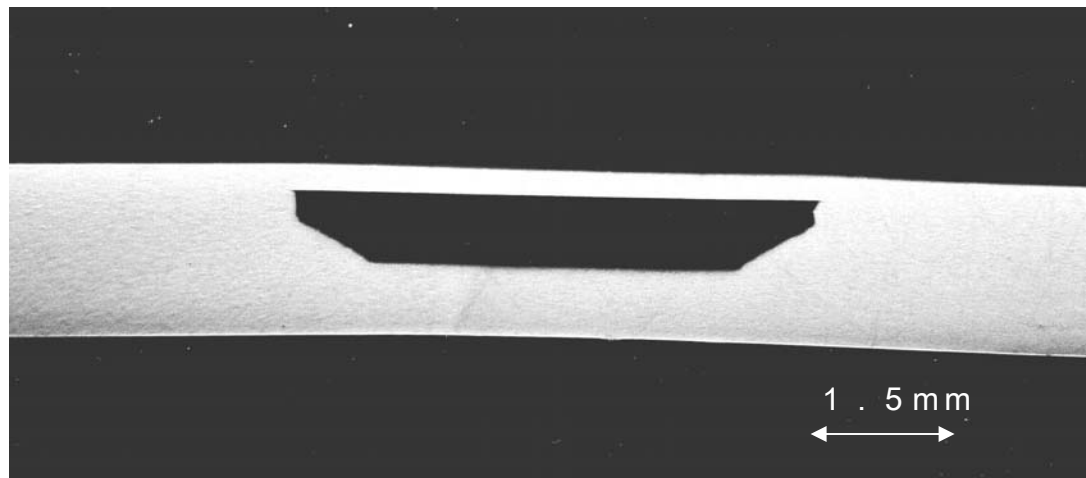
**~ Plate type tube ~**

## Trial sample of plate type tube

### ① Pattern bonding by paint patterning (BN paint)



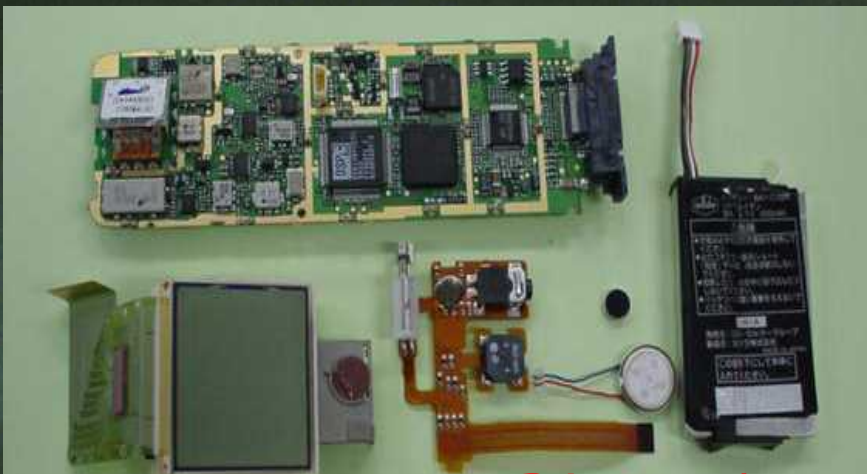
### ② Pattern bonding by cladding sheet with stamped substrate





## Example of pattern bonding after expansion treatment





**FINE CLAD is a solution  
for high density,  
low cost PWB.**

